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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/536,037
Filing Date March 27, 2000
Inventor Weimin Li et al.
Assignee Micron Technology, Inc.
Group Art Unit 2822
Examiner T. Thomas
Attorney's Docket No. MI22-1398
Title: Low K Interlevel Dielectric Layer Fabrication Methods

RESPONSE AFTER NOTICE OF ALLOWANCE
PRELIMINARY AMENDMENT TO ACCOMPANY RCE FILING

To: Box RCE
Assistant Commissioner for Patents
Washington, D.C. 20231

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)
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Responsive to the Notice of Allowance dated March 27, 2001, Applicant
remarks as follows:

REMARKS

Claims 26-33 and 52-64 are in the application for consideration.

This Request for Continued Examination (RCE) is submitted in an
abundance of caution simply to place certain references before the Examiner

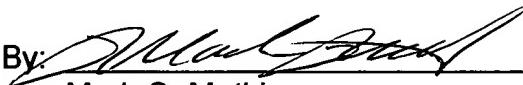
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for consideration. The references are referred to in the Supplemental Information Disclosure Statement presented herewith.

This application is believed to be in immediate condition for allowance, and action to that end is requested.

Respectfully submitted,

Dated: 4-26-01

By: 
Mark S. Matkin
Reg. No. 32,268